

TITLE OF INVENTION

PHOTORESISTS WITH HYDROXYLATED,
PHOTOACID-CLEAVABLE GROUPS

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ABSTRACT

The present invention pertains to photoimaging and the use of
photoresists (positive-working and/or negative-working) for imaging in the
production of semiconductor devices. The present invention also pertains
10 to novel hydroxy ester-containing polymer compositions that are useful as
base resins in resists and potentially in many other applications.

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